

Title (en)

A heat mode sensitive imaging element for making positive working printing plates

Title (de)

Wärmeempfindliches Aufzeichnungsmaterial zur Herstellung von positiv arbeitenden Druckplatten

Title (fr)

Matériau d'enregistrement thermosensible pour la fabrication de plaques d'impression positives

Publication

EP 0950513 A1 19991020 (EN)

Application

EP 98201216 A 19980415

Priority

EP 98201216 A 19980415

Abstract (en)

According to the present invention there is provided a heat mode imaging element for making a lithographic printing plate having on a lithographic base with a hydrophilic surface a first layer including a polymer soluble in an aqueous alkaline solution, and a top layer on the same side of the lithographic base as the first layer that is IR-sensitive and unpenetrable for an aqueous alkaline developer wherein said first layer and said top layer may be one and the same layer; characterized in that the surface of said element upon exposure and treatment with an aqueous alkaline developer is such that a) the contact angle between the unexposed areas of the imaging element and the aqueous alkaline developer changes for at most 6 DEG during the first minute of contact with said developer; b) the contact angle between the exposed areas of the imaging element and the aqueous alkaline developer changes more than 15 DEG during the first minute of contact with said developer; c) the difference in contact angle between on the one side the unexposed areas and on the other side the exposed areas of the imaging element with the aqueous alkaline solution at the onset of the measurement is not higher than 10 DEG .

IPC 1-7

B41C 1/10; **B41M 5/36**

IPC 8 full level

G03F 7/039 (2006.01); **B41C 1/10** (2006.01); **B41M 5/36** (2006.01); **B41N 1/14** (2006.01); **G03F 7/00** (2006.01)

CPC (source: EP)

B41C 1/1016 (2013.01); **B41C 2210/02** (2013.01); **B41C 2210/06** (2013.01); **B41C 2210/14** (2013.01); **B41C 2210/22** (2013.01); **B41C 2210/24** (2013.01); **B41C 2210/262** (2013.01)

Citation (search report)

- [E] EP 0864420 A1 19980916 - AGFA GEVAERT NV [BE]
- [XY] EP 0823327 A2 19980211 - MITSUBISHI CHEM CORP [JP]
- [X] GB 1245924 A 19710915 - AGFA GEVAERT [BE]
- [A] GB 1208415 A 19701014 - AGFA GEVAERT NV [BE]
- [Y] PATENT ABSTRACTS OF JAPAN vol. 014, no. 199 (P - 1040) 23 April 1990 (1990-04-23)
- [A] PATENT ABSTRACTS OF JAPAN vol. 016, no. 169 (M - 1239) 23 April 1992 (1992-04-23)

Cited by

DE19910363B4; EP1162063A3; CN110719847A; US6555291B1; US6699636B2; US11331900B2; WO0233491A3; WO0214071A1; US6613494B2; US6649324B1

Designated contracting state (EPC)

BE DE FR GB

DOCDB simple family (publication)

EP 0950513 A1 19991020; **EP 0950513 B1 20011107**; DE 69802374 D1 20011213; DE 69802374 T2 20020725; JP 2000056448 A 20000225

DOCDB simple family (application)

EP 98201216 A 19980415; DE 69802374 T 19980415; JP 10532899 A 19990413